

Citation	Summary of requirement	Am I subject to this requirement?	Explanations
§ 63.10(a)	Recordkeeping/Reporting General Requirements.	Yes	See §§ 63.7131 through 63.7133.
§ 63.10(b)(1)–(b)(2)(xii) § 63.10(b)(2)(xiii)	Records Records for Relative Accuracy Test.	Yes. No.	
§ 63.10(b)(2)(xiv) § 63.10(b)(3) § 63.10(c)	Records for Notification Applicability Determinations ... Additional CMS Record-keeping.	Yes. Yes. No	See § 63.7132.
§ 63.10(d)(1)	General Reporting Requirements.	Yes.	
§ 63.10(d)(2) § 63.10(d)(3)	Performance Test Results Opacity or VE Observations ..	Yes. Yes	For the periodic monitoring requirements in Table 6 to subpart AAAAA, report according to § 63.10(d)(3) only if VE observed and subsequent visual opacity test is required.
§ 63.10(d)(4) § 63.10(d)(5)	Progress Reports Startup, Shutdown, Malfunction Reports.	Yes. Yes.	
§ 63.10(e)	Additional CMS Reports	No	See specific requirements in subpart AAAAA, see § 63.7131.
§ 63.10(f)	Waiver for Recordkeeping/Reporting.	Yes.	Flares not applicable.
§ 63.11(a)–(b) § 63.12(a)–(c)	Control Device Requirements State Authority and Delegations.	No Yes.	
§ 63.13(a)–(c) § 63.14(a)–(b) § 63.15(a)–(b)	State/Regional Addresses Incorporation by Reference Availability of Information	Yes. No. Yes.	

**Subpart BBBB—National Emission Standards for Hazardous Air Pollutants for Semiconductor Manufacturing**

SOURCE: 68 FR 27925, May 22, 2003, unless otherwise noted.

**WHAT THIS SUBPART COVERS**

**§ 63.7180 What is the purpose of this subpart?**

This subpart establishes national emission standards for hazardous air pollutants (NESHAP) for semiconductor manufacturing facilities. This subpart also establishes requirements to demonstrate initial and continuous compliance with the emission standards.

**§ 63.7181 Am I subject to this subpart?**

(a) You are subject to this subpart if you own or operate a semiconductor manufacturing process unit that is a major source of hazardous air pollutants (HAP) emissions or that is located

at, or is part of, a major source of HAP emissions.

(b) A major source of HAP emissions is any stationary source or group of stationary sources located within a contiguous area and under common control that emits or has the potential to emit, considering controls, in the aggregate, any single HAP at a rate of 10 tons per year (tpy) or more or any combination of HAP at a rate of 25 tpy or more.

**§ 63.7182 What parts of my facility does this subpart cover?**

(a) This subpart applies to each new, reconstructed, or existing affected source that you own or operate that manufactures semiconductors.

(b) An affected source subject to this subpart is the collection of all semiconductor manufacturing process units used to manufacture p-type and n-type semiconductors and active solid-state devices from a wafer substrate, including research and development activities integrated into a semiconductor